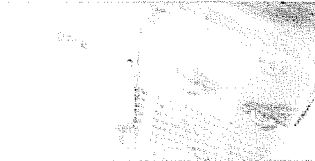


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**EATON NOVA / AXCELIS****ION IMPLANTERS & MONITORS**

20 I

&lt; previous | next &gt;

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EATON NOVA / AXCELIS 10-160 High Current Implanter, refurbished except for gas box, can be inspected and demonstrated, can be configured for 4"-6", DataLock II with Auto Tune II, Cassette-to-cassette wafer loader, Vacuum pick-up Disk Exchange Arms, Electron shower, Remote Arc Voltage Selection, Enhanced Source with Dual Vaporiser, Four Bottle Gas Box with VCR Fittings and Safety Bypass Valves, Solid State Switching Power Supply (Extraction), FastScan System, Clampless Disks, Autoclean, CE marked, connected to electrical power but not in cleanroom, 1995 vintage. (1) **\$250**

EATON NOVA / AXCELIS 10-160 Implanter, 6" AT4 handler, Vacuum Exchange Arms, Source diffusion pump, Onboard8 cryopumps, Source Drypump, Fastscan, Rev3 flood gun, White ion source, still running, fully operational, can be inspected, as-is. Service and installation can be provided. (1) **\$175**

EATON NOVA / AXCELIS 10-160 Implanter, refurbished, crated and ready to ship. Includes installation. (1) **\$270**

EATON NOVA / AXCELIS 10-160 Implanter, Refurbished with warranty. (1) **\$350**

EATON NOVA / AXCELIS 10-160 Implanter, under power, could be tested with toxic gas. (1) **Inquiry**

EATON NOVA / AXCELIS 10-80 Eaton High Current 6", AT-4, Clampless, Datalogger, PM'd & Decontaminated, Installation, warranty can be made available. (4) **\$60,000**

EATON NOVA / AXCELIS 10-80 implanters. (4) **Inquiry**

EATON NOVA / AXCELIS 10-80A Implanter, 6" (1) **\$25,000**

EATON NOVA / AXCELIS 6200 Medium Current Implanter, running in fab, can be demonstrated, 6". (1) **\$446**

EATON NOVA / AXCELIS 6200 Medium Current Implanters. (7) **Inquiry**

EATON NOVA / AXCELIS 6200A Medium Current Implanter, refurbished. (1) **Inquiry**

EATON NOVA / AXCELIS GSD 200E 180 KEV High Current implanter, 8", Enhanced Bernas source w/ Dual Vaporizers, Bypass Valves and Nitrogen Purge, Variable Aperture Extraction Electrode, Enhanced Low Energy Beamline, 80kV Single Stage Extraction, Triple Indexed Mass Analysis Magnet and Power Supply, 80kV Post Acceleration Electrode Assembly (180kV system only), Flag Faraday, Slot-to-Slot Load Upgrade, NV-GSD/200 Series End Station Four Cassette Capacity, Automatic Notch Alignment Capability with Buffer Cassette, Integrated Dummy Wafer Fill-In Capacity, In-Air, In-Vacuum High Throughput Wafer Handling system, Class 1, ULPA Filtered Wafer Handling Area, Two Axis Variable Implant Angle (+/- 11 deg in each axes), GSD Series Process Disk(with Active Cooling and External Closed Loop Chiller), Disk Removal Tool, Real-Time Patented Dose Control, Real-Time Beam Profiler, Electron Shower w/ Gas Bleed and Closed Loop control, In Situ Water Charge Monitor, Advanced Automation Package, Sun SPARC Operator Workstation Hard Drive, Tape Cartridge, 19" Color Monitor and Laser Printer, Automatic Beam Tuning and Set-up using Eaton Autotune Software, Automated Chained Implant Capacity, SECS I and SECS II Protocols, and GEM Interface, On-line Help and On-line Maintenance Advisory, Laser Printer, Vacuum System, Source High Vac Pump 1 (P1) - Seiko 1000i/s, Source Roughing Pump (RP1) - Ebara Dry Pump 40x20 CFM, End Station Cryo Pump (P2) - CTI On-Board10, Fast Regen, Beamline Cryo Pump (P3) - CTI On-Board8, Fast Regen, End Station Roughing Pump (RP2/3) - Ebara A70W, Gas Box Options 3- MKS 1640 Pressure Flow Controllers, 180keV Upgrade Package, Additional Remote Sun SPARC Workstation, Disk Chiller Option, Real Time Particle Detection System (Fully Integrated HYT), Automated SPC Data Collection and Analysis, Cassette Bar Code Reading System, Lead Floor, Complete Fast Maintenance Kit, Spare ELS Source, Variable Aperture Extraction Electrode, Insulating Bushing, Source Mounting Flange Assembly, Flag Faraday Assembly, Electron Shower, Source Liner, 1997 vintage. Currently decontaminated, deinstalled and crated to OEM standards. (1)

Inqui

EATON NOVA / AXCELIS GSD 200E2 90 KEV High Current implanter, 8", ELS (Moly) Ion source, Bypass Valves and Nitrogen Purge, Variable Aperture Extraction Electrode, Enhanced Low Energy Beamline(GSD/200E2), 80kV Single Stage Extraction, Triple Indexed Mass Analysis Magnet and Power Supply, 80kV Post Acceleration Electrode Assembly (180kV system only), Injector Flag Faraday, GSD Series End Station, Four Cassette Capacity, Automatic Notch Alignment Capability with Buffer Cassette, Integrated Dummy Wafer Fill-In Capacity, In-Air, In-Vacuum High Throughput Wafer Handling system, Class 1, ULPA Filtered Wafer Handling Area, Two Axis Variable Implant Angle (+/- 11 deg in each axes for Quad Implant), GSD Series Process Disk(with Active Cooling and External Closed Loop Chiller), Direct Drive Subsystem for the process disk, Real-Time Patented Dose Control, Charge Control Technology w/ Gas Bleed - Xenon Plasma, In Situ Water Charge Monitor, Advanced Automation Package, Sun SPARC Operator Workstation, Hard Drive, Tape Cartridge, 19" Color Monitor and Laser Printer, Automatic Beam Tuning and Set-up using Eaton Autotune Software, Automated Chained Implant Capacity, SECS I and SECS II Protocols, and GEM Interface, On-line Help and On-line Maintenance Advisory, Vacuum System, Source High Vac Pump 1 (P1) - Seiko 2000i/s TMP, Source Roughing Pump (RP1) - Ebara Dry Pump 40x20 CFM, End Station Cryo Pump (P2) - CTI On-Board8, Fast Regen, Beamline Cryo Pump (P3) - CTI On-Board10, Fast Regen, End Station Roughing Pump (RP2/3) - Ebara A70W, Gas Box MFC Options: MKS 1179 High Pressure MFC, MKS 1540 PFC with MKS 750 Pressure Transducer (3), Complete Fast Maintenance Kit, Spare ELS Source, Variable Aperture Extraction Electrode, Insulating Bushing, Source Mounting Flange Assembly, Flag Faraday Assembly, Or PEF - Primary Electron Flood, Remote Sun SPARC Workstation, Real Time Particle Detection System (Fully Integrated HYT), Remote Disk Chiller Option, Cassette Bar Code Reading System, Lead Floor, Source Liner, Slot-to-Slot Wafer Position Integrity, 1999 vintage. (1)

Inqui

EATON NOVA / AXCELIS GSD 80 Implanters. (2)

Inqui

EATON NOVA / AXCELIS GSD III-LE High Current Ion Implanter, 2000 vintage. (1)

Inqui

EATON NOVA / AXCELIS GSD III-LED high current implanter (low energy)Ultra Style, 80 kV, Enhancements Enhanced Low Energy Beamline, Low Energy ELS (Inverted)(Tungsten), Bypass Valves and Nitrogen Purge, Dual slit, decel Extraction Electrode, Enhanced Low Energy Decel Beamline and Optics, Dual-Range High Voltage Power Supply, 0-10kV low and 10-80kV high, 90 Degree Mass Analysis Magnet and Power Supply, Electron Confinement Beamguide and Beam Tunnel, 3-

Position Selectable Resolving Aperture with Deceleration Electrode, Smoke detectors, "Control power on" rear beacons (2 amber), Front and rear audible alarms, New GSD Series End Station, Four Cassette Capability, Wafer Size of 8", Automatic Flat or Notch Alignment Capability with Buffer Cassette, In-Air/In-Vacuum High Throughput Wafer Handling System, Class 1, ULPA Filtered Wafer Handling Area, Two Axis Variable Implant Angle ( $\pm 10^\circ$  in two axes)(Quad Implant Capability), GSD Series "Direct Drive" Process Disk (installed), Real-Time Patented Dose Control, Real-Time Beam Profiler, PEF-Xe Charge Control Technology With Gas Bleed, Si Coated Virtual Slot Disk, Triple Surface Disk Faraday, In Situ Beam Potential Monitor, Advanced Automation Package, Solaris Operator Workstation, Hard Drive, Tape Cartridge, Color Monitor and Laser Printer, Automatic Beam Tuning and Set-up using Axcelis Autotune<sup>TM</sup> software, Automated Chained Implant Capability, Automated SPC Data Collection and Analysis Software Package, SECS I and SECS II Protocols, GEM Interface, and Ethernet Port, On-line Help and On-line Maintenance Advisory, Four String Gas Box Option, Two High Pressure Gasbox Strings, Two SDS Gasbox Strings, Two Pressure Transducers for SDS strings, Two MKS1179B HP Mass Flow Controllers. (2)

Inqui

EATON NOVA / AXCELIS GSD ULE2 low energy implanter, currently running in R&D, Dose Uniformity: Within wafer 1 $\sigma$  - < 0.75% @ > 5 keV, Wafer to wafer 1 $\sigma$  - < 1.0% @ < 5 keV, can be inspected, 1997 vintage. (1)

Inqui

EATON NOVA / AXCELIS HC3 high current ion implanter (low energy), 12", 13 wafer batch, 4 PDOs, Full 300mm factory automation, Enhance Low Energy Beamline, Modified ELS (Extended Life Source), Moly, Bypass Valves and Nitrogen Purge, Dual Slit Extraction Electrode, Enhanced Low Energy Beamline and Optics, 80kV Extraction Potential and Total Beam Energy Range of 200eV - 80keV, Precision Dual-Range Extraction Power Supply, 90 Degree Mass Analysis Magnet and Power Supply, Decel Power Supply, 3-Position Selectable Resolving Aperture with Deceleration Electrode, PEF-Xe Charge Control Technology With Gas Bleed, Flag Faraday Assy, Triple Surface Disk Faraday (TSDF), HC3 End Station, 4-FOUP Capability, 13 Wafer Batch End Station, In-Air/In-Vacuum High Throughput Wafer Handling System, Sub-Class 1, ULPA Filtered (99.99995% @ 0.7 $\mu$ m Efficiency) Wafer Handling Area, Automatic Notch Alignment Capability with Buffer Cassette, Integrated "Dummy Wafer" Fill-in Capability, Two Axis Variable Implant Angle ( $\pm 7^\circ$  in two axes)(Quad Implant Capability), Three CTI-250F On-Board Cryo Pumps (P3, P9, P11) and Two 9600 Compressors, SIG Ion Gauge in IG3 location, Virtual Slot Water Integrity (as Standard), Real-Time Patented Dose Control, In-situ Beam Potential Monitor, Beam Profiler, Advanced Automation Package, including: Sun Solaris Operator Workstation with Hard Drive, Tape Cartridge, Flat Panel Color Monitor and Laser Printer, Automatic Beam Tuning and Set-up using Axcelis Autotune, Automated SPC Data Collection and Analysis, Rear Mounted Flashing High Voltage Beacon, Upgrades: Ultra 5.5 Beamline, Loadlock Rough Optimization (FM) aka Block 2 Minienvironment, ionizer Eterna Source (without vaporizer), SRA Cooling upgrade, P1 turbo mounting bracket, RP1 Fast Acting Valve, V6 Cell Controller, Electrode Manipulator / Decel Insulator, Minienvironment doors, Disk faraday fiber optics, Extraction electrode upgrade, Hall Probe PCB, Wafer Aligner bracket and harness upgrade, Chiller upgrade, Sliding seal plate upgrade, Yaskawa robot upgrade, PEF Reliability upgrade, High Voltage System Grounding upgrade, Source Isolation Valve (V2) upgrade, Seiko "C2" turbo upgrade, Seiko TMS (heated) source turbo upgrade, Power Dose DI Current, SW Rev 2.5 2D, Beam Profile Interlock, 2002 vintage. (2)

Inqui

EATON NOVA / AXCELIS HC3 Ultra 5.5 ion implanter, 12" wafer, 13 wafer batch, 4 PDOs, full 12" factory automation, excellent condition. (1)

Offer

EATON NOVA / AXCELIS NV 6200A Medium Current Implanter, 5", refurbished, 1989 vintage. (1)

Inqui

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